

SHEET 1 OF 2

FORM PTO-1449 (Rev. 2-32)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. SMA-001	SERIAL NO. 09/425,494
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT REDDY	
(USE SEVERAL SHEETS IF NECESSARY)		FILING DATE 10/22/99	GROUP 2811



U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
K.N. A	4,786,907	Nov. 22, 1988	Koelle	342	51	Jul. 14, 1986
K.N. B	4,816,839	Mar. 28, 1989	Landt	343	795	Dec. 18, 1987
K.N. C	4,877,641	Oct. 31, 1989	Dory	427	38	May 31, 1988
K.N. D	4,910,499	Mar. 20, 1990	Benge, et al.	340	572	Feb. 10, 1989
K.N. E	5,346,850	Sep. 13, 1994	Kaschmitter, et al.	437	81	Oct. 29, 1992
K.N. F	5,444,223	Aug. 22, 1995	Blama	235	435	Jan. 11, 1994
K.N. G	5,528,222	Jun. 18, 1996	Moskowitz, et al.	340	572	Sep. 9, 1994
K.N. H	5,572,226	Nov. 5, 1996	Tuttle	343	726	Apr. 11, 1995
K.N. I	5,708,419	Jan. 13, 1998	Isaacson, et al.	340	572	Jul. 22, 1996
K.N. J	5,779,839	Jul. 14, 1998	Tuttle, et al.	156	213	Sep. 26, 1997

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	PUB. DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES NO
K						
L						
M						
N						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL	
K.N. O	"1994 Display Manufacturing Technology Conference Digest of Technical Papers", Society for Information Display, First Edition, January, 1994, 16 pages.
K.N. P	"1994 Seminar Lecture Notes", Society for Information Display, Volume I: June 13, 1994, Figures 1-44, 23 pages.
K.N. Q	"1995 Display Manufacturing Technology Conference Digest of Technical Papers", Society for Information Display, First Edition, January, 1995, 16 pages.
K.N. R	"An Amorphous Silicon Thin Film Transistor Fabricated at 125°C by DC Reactive Magnetron Sputtering", C.S. McCormick, et al., Appl. Phys. Lett. 70 (2), 13 January 1997, 1997 American Institute of Physics.
K.N. S	"Low Temperature Fabrication of Amorphous Silicon Thin Film Transistors by DC Reactive Magnetron Sputtering", C.S. McCormick, et al., J. Vac. Sci. Technol. A 15(5), Sep/Oct 1997, 1997 American Vacuum Society.

EXAMINER

K. Newman

DATE CONSIDERED

12/20/02

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



SHEET 2 OF 2

FORM PTO-1449 (Rev. 2-32)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. SMA-001	SERIAL NO. 09/425,494
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROP.
KN	A 5,786,626	Jul. 28, 1998	Brady, et al.	257	673	Mar. 25, 1996
KN	B 5,796,121	Aug. 18, 1998	Gates	257	59	Mar. 25, 1997
KN	C 5,817,550	Oct. 6, 1998	Carey, et al.	438	166	Mar. 5, 1996
KN	D 5,856,858	Jan. 5, 1999	Carey, et al.	349	158	Dec. 1, 1997
KN	E 5,912,632	Jun. 15, 1999	Dieska, et al.	340	825.54	Jan. 8, 1997
KN	F 5,929,760	Jul. 27, 1999	Monahan	340	572.7	Oct. 20, 1997
KN	G					
KN	H					
KN	I					
KN	J					

FOREIGN PATENT DOCUMENTS

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						YES NO
K						
L						
M						
N						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL	DOCUMENT NUMBER	DATE
KN	O "Chapter 3, Manufacturing and Infrastructure of Active Matrix Liquid Crystal Displays", Malcolm Thompson, 12/10/97.	
KN	P "PolySilicon Thin Film Transistors Fabricated at 100°C on a Flexible Plastic Substrate", YIJ. Tung, et al.,	
KN	Q "RFID: Card Manufacturing Fundamentals", Michael L. Davis, 10/11/99, 53 pages of slides.	
KN	R "Computer Display Industry and Technology Profile", Display Industry and Technology Profile, 7/28/99, 59 pages.	
KN	S	

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Thiemnguyen

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12/20/02

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